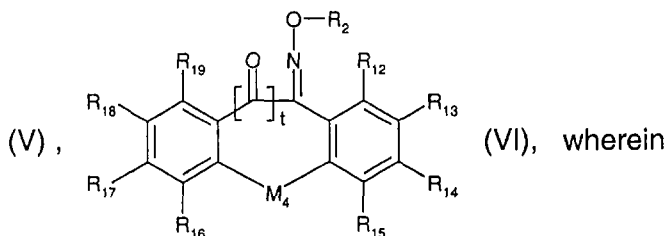
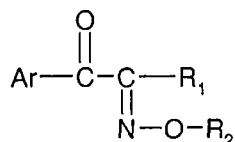
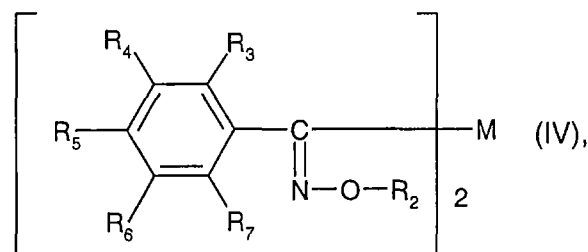
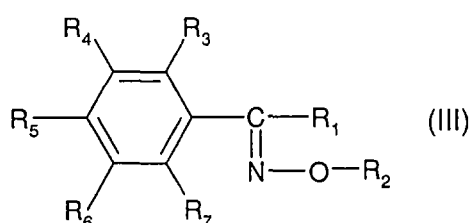
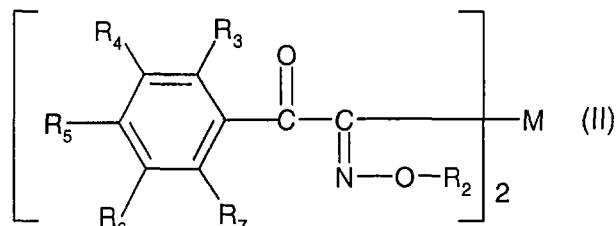
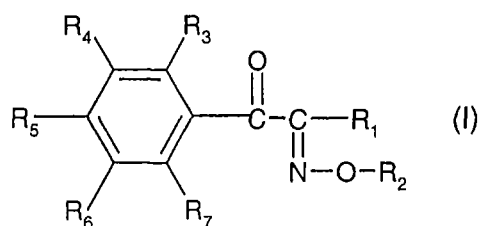


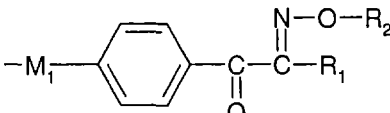
Abstract

Compositions comprising

- (A) an oligomer or polymer containing at least one carboxylic acid group in the molecule;
 (B) at least one compound of the formula I, II, III, IV, V or VI



R_1 inter alia is phenyl or alkyl; R_2 is for example C_2 - C_{12} alkanoyl which is unsubstituted or substituted or is benzoyl; R_3 , R_4 , R_5 , R_6 and R_7 independently of one another are for instance hydrogen, C_1 - C_{12} alkyl, cyclohexyl or phenyl which is unsubstituted or substituted, or are benzyl, benzoyl, C_2 - C_{12} alkanoyl or phenoxy carbonyl; R_8 is for example hydrogen or C_1 -

C_{12} alkyl or a group $\text{---M}_1\text{---}$ ; M is for example C_1 - C_{12} alkylene,

cyclohexylene or phenylene; M_1 inter alia is a direct bond or C_1 - C_{12} alkylenoxy; and Ar is a 5- or 6-membered aromatic heterocyclic ring;

(C) a photopolymerizable reactive or unreactive diluent; and

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(D) as a thermosetting component an epoxy compound containing at least two epoxy groups in one molecule;
are highly suitable as resists which are alkaline developable.